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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/804,353	03/18/2004	Robert Rozbicki	NOVLP024X2/NVLS-2852	9231
22434 7.	590 10/03/2005		EXAMINER	
	VER & THOMAS L	GURLEY, LY	GURLEY, LYNNE ANN	
P.O. BOX 702: OAKLAND. (50 CA 94612-0250		ART UNIT	PAPER NUMBER
, ,			2812	
			DATE MAILED: 10/03/2005	

Please find below and/or attached an Office communication concerning this application or proceeding.

		Application No.	Applicant(s)			
		10/804,353	ROZBICKI ET AL.			
	Office Action Summary	Examiner	Art Unit	·		
		Lynne A. Gurley	2812			
Period fo	The MAILING DATE of this communication app or Reply	pears on the cover	sheet with the correspondence address			
A SHOWHIC - Exter after - If NO - Failu Any r	ORTENED STATUTORY PERIOD FOR REPLICHEVER IS LONGER, FROM THE MAILING Designs of time may be available under the provisions of 37 CFR 1.1 SIX (6) MONTHS from the mailing date of this communication. period for reply is specified above, the maximum statutory period or to reply within the set or extended period for reply will, by statute reply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS CON 36(a). In no event, however will apply and will expire Store, cause the application to the	MMUNICATION. er, may a reply be timely filed X (6) MONTHS from the mailing date of this communication. become ABANDONED (35 U.S.C. § 133).			
Status						
1)🖾	Responsive to communication(s) filed on 18 M	larch 2004.				
2a) <u></u> □	This action is FINAL . 2b)⊠ This	s action is non-final				
3)	•					
	closed in accordance with the practice under E	Ex parte Quayle, 19	935 C.D. 11, 453 O.G. 213.			
Dispositi	ion of Claims					
5)□ 6)⊠ 7)□	Claim(s) 1-23 is/are pending in the application 4a) Of the above claim(s) is/are withdra Claim(s) is/are allowed. Claim(s) 1-23 is/are rejected. Claim(s) is/are objected to. Claim(s) are subject to restriction and/or	wn from considera				
Applicati	ion Papers					
,—	The specification is objected to by the Examine The drawing(s) filed on is/are: a) acc Applicant may not request that any objection to the	cepted or b) objection of the drawing (s) be held in	abeyance. See 37 CFR 1.85(a).	,		
11)□	Replacement drawing sheet(s) including the correct The oath or declaration is objected to by the Ex)·		
Priority ι	under 35 U.S.C. § 119					
a)(Acknowledgment is made of a claim for foreign All b) Some * c) None of: 1. Certified copies of the priority document 2. Certified copies of the priority document 3. Copies of the certified copies of the priority document application from the International Bureasee the attached detailed Office action for a list	ts have been recei ts have been recei ority documents ha u (PCT Rule 17.2(ved. ved in Application No ve been received in this National Stage			
		·	Month Stale	_		
2) Notice 3) Information	ot(s) Due of References Cited (PTO-892) Due of Draftsperson's Patent Drawing Review (PTO-948) The mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) The results of the control of	, F (5 1	PRIMARY PATENT EXAMINER TC 2800, AU 2812 Interview Summary (PTO-413) Paper No(s)/Mail Date Notice of Informal Patent Application (PTO-152) Other:			

DETAILED ACTION

Specification

1. The specification has not been checked to the extent necessary to determine the presence of all possible minor errors. Applicant's cooperation is requested in correcting any errors of which applicant may become aware in the specification.

Claim Rejections - 35 USC § 102

2. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

- (e) the invention was described in (1) an application for patent, published under section 122(b), by another filed in the United States before the invention by the applicant for patent or (2) a patent granted on an application for patent by another filed in the United States before the invention by the applicant for patent, except that an international application filed under the treaty defined in section 351(a) shall have the effects for purposes of this subsection of an application filed in the United States only if the international application designated the United States and was published under Article 21(2) of such treaty in the English language.
- 3. Claims 1-2, 6-8, 16-19, 21-22 are rejected under 35 U.S.C. 102(e) as being anticipated by Gopalraja et al. (US 6,274,008, dated 8/14/01, filed 10/2/00).
- 4. Gopalraja shows the method as claimed, in figures 14-16, as: (a) etching the bottoms of recessed features (218/212; figs. 14-15) on a surface of the substrate 210 to clean at least part of an underlying metal while simultaneously depositing a first portion of a diffusion barrier on at least sidewalls of recessed features (fig. 15); (b) depositing a second portion of the diffusion barrier 228, which covers at least the bottoms of the recessed features; and (c) depositing the metal conductive layer (column 14, lines 18-30) over the surface of the substrate. Preclean is not necessary (column 5, lines 1-4).

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5. Claims 1-2, 6-8, 16-17 and 21-22 are rejected under 35 U.S.C. 102(e) as being anticipated by Hashim et al. (US 6,287,977, dated 9/11/01, filed 7/31/98).

6. Hashim shows the method as claimed in figures 1-10 and corresponding text, with emphasis on figures 4A-4D, as: (a) etching the bottoms of recessed features (55/57; fig. 4A) on a surface of the substrate to clean at least part of an underlying metal while simultaneously depositing a first portion of a diffusion barrier on at least sidewalls of recessed features (fig. 4B); (b) depositing a second portion of the diffusion barrier 61, which covers at least the bottoms of the recessed features; and (c) depositing the metal conductive layer (57b) over the surface of the substrate.

Claim Rejections - 35 USC § 103

- 7. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 8. The factual inquiries set forth in *Graham* v. *John Deere Co.*, 383 U.S. 1, 148 USPQ 459 (1966), that are applied for establishing a background for determining obviousness under 35 U.S.C. 103(a) are summarized as follows:
 - 1. Determining the scope and contents of the prior art.
 - 2. Ascertaining the differences between the prior art and the claims at issue.
 - 3. Resolving the level of ordinary skill in the pertinent art.
 - 4. Considering objective evidence present in the application indicating obviousness or nonobviousness.

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9. This application currently names joint inventors. In considering patentability of the claims under 35 U.S.C. 103(a), the examiner presumes that the subject matter of the various claims was commonly owned at the time any inventions covered therein were made absent any evidence to the contrary. Applicant is advised of the obligation under 37 CFR 1.56 to point out the inventor and invention dates of each claim that was not commonly owned at the time a later invention was made in order for the examiner to consider the applicability of 35 U.S.C. 103(c) and potential 35 U.S.C. 102(e), (f) or (g) prior art under 35 U.S.C. 103(a).

- 10. Claims 3-5, 9-15, 20 and 23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Gopalraja et al. (US 6,274,008, dated 8/14/01, filed 10/2/00).
- 11. Gopalraja shows the method substantially as claimed, and as described in the previous paragraphs.
- 12. Gopalraja lacks anticipation only in not teaching an additional etching step for the barrier layer; a degas operation prior to (a); aspect ratios; a hollow cathode magnetron processing chamber; heating while degassing; depth of the etching of the bottom of the recessed features; etch-to-deposition ratio; thicknesses; claimed power ranges; and flow rates.
- 13. It would have been obvious to one of ordinary skill in the art to have had a degas operation prior to (a); the claimed aspect ratios; a hollow cathode magnetron processing chamber; heating while degassing; the claimed depth of the etching of the bottom of the recessed features; the claimed etch-to-deposition ratio; thicknesses; claimed power ranges; and flow rates, in the method of Gopalraja, with the motivation that a magnetron device is disclosed (column 1, lines 59-67; column 4, lines 48-53; column 6), so that the specific type of magnetron processing

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apparatus would be a matter of design choice; and, with the motivation that the additional claimed ranges and features are parameters of optimization to one of ordinary skill in the art.

14. Claims 3-5, 9-15, 18-20 and 23 are rejected under 35 U.S.C. 103(a) as being unpatentable over Hashim et al. (US 6,287,977, dated 9/11/01, filed 7/31/98).

Hashim shows the method substantially as claimed, and as described in the previous paragraphs.

15. Hashim lacks anticipation only in not teaching an additional etching step for the barrier layer; a degas operation prior to (a); aspect ratios; a hollow cathode magnetron processing chamber; heating while degassing; depth of the etching of the bottom of the recessed features; etch-to-deposition ratio; thicknesses; claimed power ranges; and flow rates.

It would have been obvious to one of ordinary skill in the art to have had a degas operation prior to (a); the claimed aspect ratios; a hollow cathode magnetron processing chamber; heating while degassing; the claimed depth of the etching of the bottom of the recessed features; the claimed etch-to-deposition ratio; thicknesses; claimed power ranges; and flow rates, in the method of Hashim, with the motivation that a sputtering chamber is disclosed, so that the specific type of sputtering apparatus, including a magnetron sputtering apparatus, would be a matter of design choice; and, with the motivation that degassing is disclosed and the additional claimed ranges and features are parameters of optimization to one of ordinary skill in the art.

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Conclusion

16. The prior art made of record and not relied upon is considered pertinent to applicant's

disclosure. See the PTO Form 892.

Any inquiry concerning this communication or earlier communications from the

examiner should be directed to Lynne A. Gurley whose telephone number is 571-272-1670. The

examiner can normally be reached on M-F 7:30-4:00.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's

supervisor, Michael Lebentritt can be reached on 571-272-1873. The fax phone number for the

organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent

Application Information Retrieval (PAIR) system. Status information for published applications

may be obtained from either Private PAIR or Public PAIR. Status information for unpublished

applications is available through Private PAIR only. For more information about the PAIR

system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR

system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

Lynne A. Gurley

Primary Patent Examiner

gue A. Gurly

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LAG

September 29, 2005